LETTERS

Novel light sputter ion pump with neodymium iron boron magnets and the low outgassing body
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Microstructure analysis of plasma enhanced atomic layer deposition-grown mixed-phase RuTaN barrier for seedless copper electrodeposition
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REVIEW ARTICLE

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Growth morphology and electrical/optical properties of Al-doped ZnO thin films grown

by atomic layer deposition
Tara Dhakal, Daniel Vanhart, Rachel Christian, Abhishek Nandur, Anju Sharma and Charles R. Westgate
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Populations of metastable and resonant argon atoms in radio frequency magnetron plasmas used for deposition of indium-zinc-oxide films
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***In situ* fabrication of blue ceramic coatings on wrought Al Alloy 2024 by plasma electrolytic oxidation**
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Blueshift in sulfur treated GaAsP/AlGaAs near surface quantum well
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Tribological behavior of Ti-Al-Si-C-N hard coatings deposited by hybrid arc-enhanced magnetron sputtering
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Twin structures of epitaxial SnO_2 films grown on a-cut sapphire by metalorganic chemical vapor deposition
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Plasma-enhanced and thermal atomic layer deposition of Al_2O_3 using dimethylaluminum isopropoxide, $[Al(CH_3)_2(\mu\text{-}O^iPr)]_2$, as an alternative aluminum precursor
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